

“Complementi di Fisica”
Lecture 5



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Course Outline - Reminder

- The physics of semiconductor devices: an introduction
 - Basic properties; energy bands, density of states
 - Equilibrium carrier concentration (“intrinsic”, “extrinsic”)
 - Carrier transport phenomena
 - Drift and Diffusion
 - Generation and Recombination
 - Continuity equations
- Quantum Mechanics: an introduction
- Advanced semiconductor fundamentals



Lecture 5 - outline

- Carrier diffusion
 - Diffusion process: current density and diffusivity
 - Einstein relation between diffusivity and mobility
 - Current density equations
- Carrier injection
 - Majority, minority and excess carriers
- Generation and recombination: individual processes
 - Direct recombination
 - Indirect recombination
 - Surface recombination
- Next lecture:
 - continuity equations: all effects together (drift, diffusion, generation, recombination); three important special cases
 - high field effects



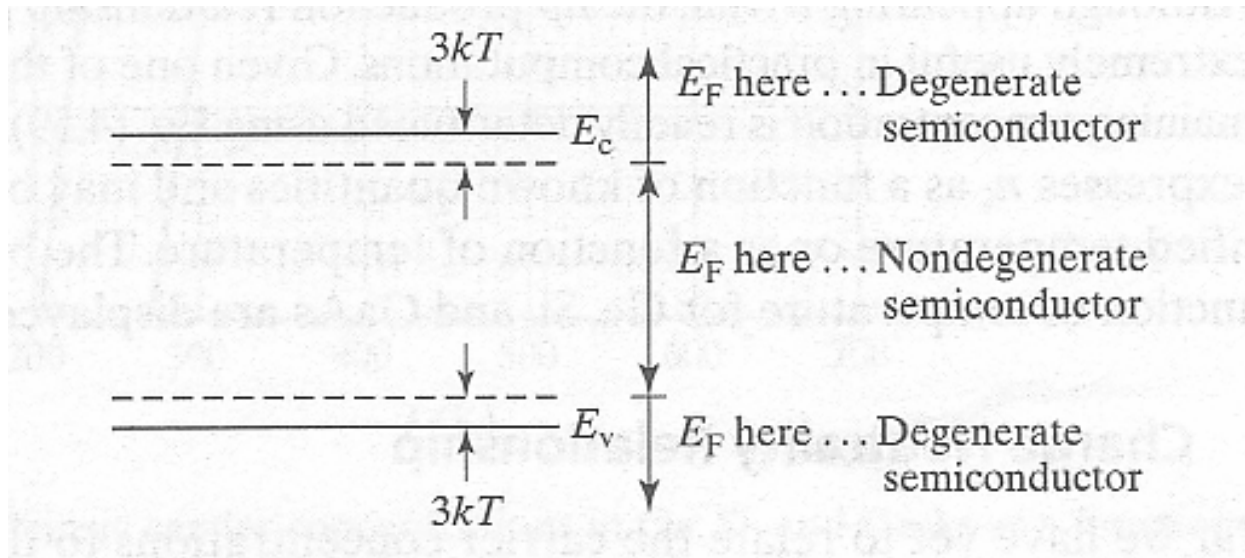
Lecture 5 – warning / 1

- All equations will be derived and written in a simplified 1-dimensional case
 - Carrier concentrations varying only along x coordinate:
 - $n(x)$, $p(x)$
 - Current density only in x direction
 - J_x
 - Derivatives with respect to x
 - d/dx
- They can be generalized to the general 3-dimensional case (see later)
 - $n(x,y,z)$, $p(x,y,z)$
 - J_x , J_y , J_z
 - Partial derivatives, differential operators (div, grad)



Lecture 5 – warning / 2

- “Non-degenerate” and “degenerate” semiconductors
 - Definition:



- Consequences:
 - For “non-degenerate semiconductors” the approximate form (Boltzmann) of the Fermi function can be used
 - Equations are simpler in this case! we will continue our discussion in this limit, to avoid obscuring the physics

Diffusion

Current density and diffusivity

Drift and diffusion together

Einstein relation

Current density equations

Diffusion process

- **Qualitatively:**

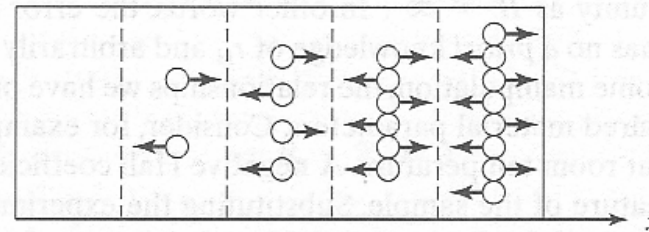
- *If* there is a space variation of carrier concentration in the semiconductor material: *then* carriers tend to move predominantly from a region of high concentration to a region of low concentration

Microscopic scale: in each section,

- equal out-flow to $+x$ and $-x$
- different in-flow from right and left

Net effect:

carrier concentrations tend to level out



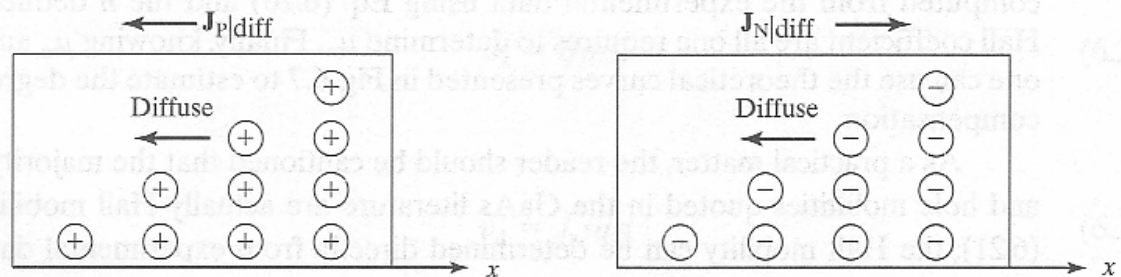
(a)

Macroscopic scale:

current densities

$J_{n,diff}$

$J_{p,diff}$



(b)



Diffusion process

- Quantitatively, for electrons:

Left to right through plane at $x = 0$

$$F_1 = \frac{1}{2} \frac{n(-l)l}{\tau_c} = \frac{1}{2} n(-l)v_{th}$$

Right to left through the same plane

$$F_2 = \frac{1}{2} n(l)v_{th}$$

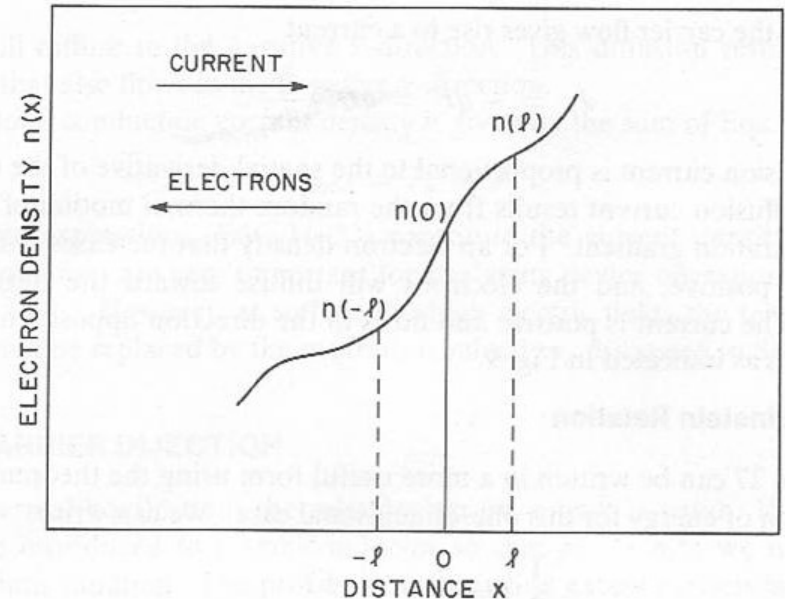
Net rate of carrier flow at $x = 0$

$$F = F_1 - F_2 = \frac{1}{2} v_{th} [n(-l) - n(l)] =$$

$$= -v_{th} l \frac{dn}{dx} \equiv -D_n \frac{dn}{dx}$$

$$l = v_{th} \tau_c$$

Thermal motion:
mean free path =
thermal velocity \times
 \times mean free time



Taylor series
expansion:

$$n(-l) = n(0) - l \left(\frac{dn}{dx} \right)_{x=0}$$

$$n(l) = n(0) + l \left(\frac{dn}{dx} \right)_{x=0}$$



Diffusion equations

- Diffusion current, electrons (1-dimensional case):

$$J_{n,x} = -|q|F = |q|D_n \frac{dn}{dx}$$

if positive gradient
 $dn/dx > 0$
then: positive current
 $J_{n,x} > 0$

- Similarly, holes:

$$J_{p,x} = |q|F = -|q|D_p \frac{dp}{dx}$$

if positive gradient
 $dp/dx > 0$
then: negative current
 $J_{p,x} < 0$

- Diffusivity:

$$D_n \equiv v_{th,n} l_n \quad D_p \equiv v_{th,p} l_p$$

Dimensionally OK;
a more complete 3-d
analysis gives a
numerical coefficient
(1/3)



Drift and diffusion together

Drift and diffusion: Einstein relation

- Drift (mobility) and diffusion (diffusivity) coefficients are correlated!

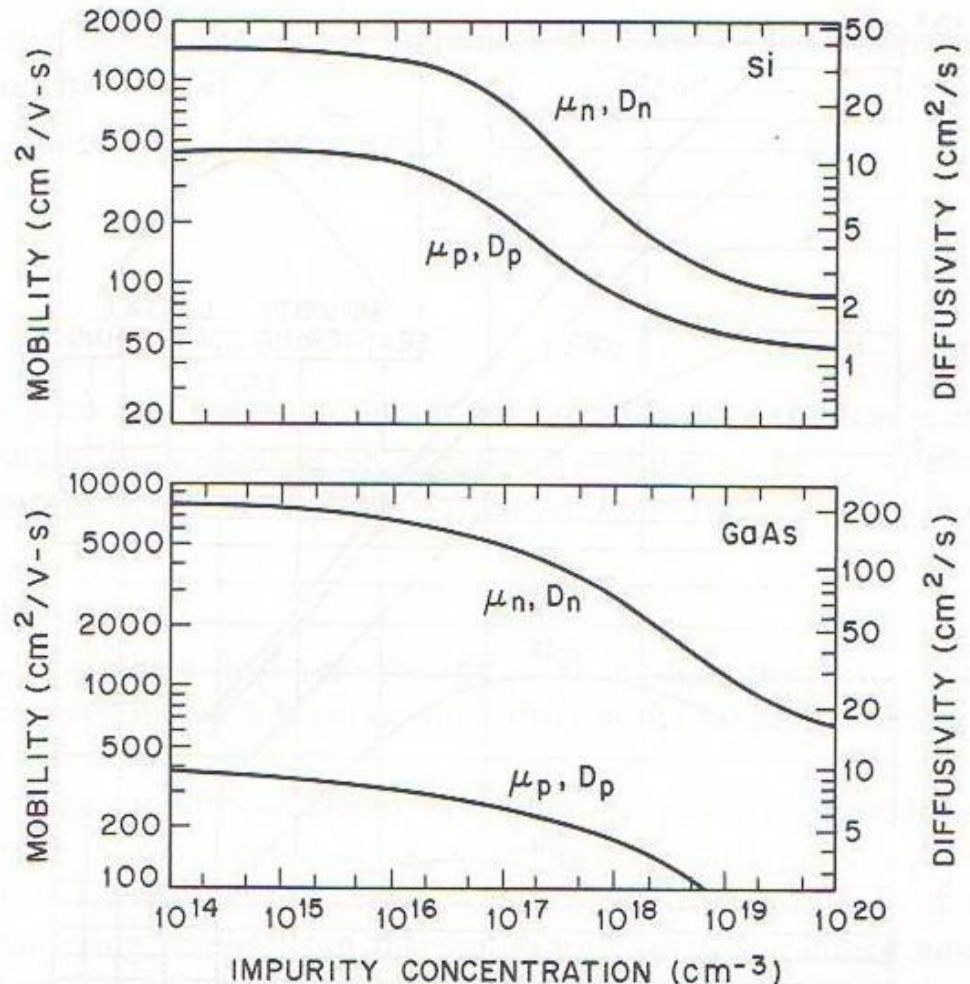
thermal velocity $\rightarrow D \equiv v_{th} l$

drift velocity $\rightarrow v_n = -\mu_n E$

external field $\rightarrow v_p = \mu_p E$

$$D_n = \left(\frac{kT}{q} \right) \mu_n \quad D_p = \left(\frac{kT}{q} \right) \mu_p$$

- Why ?
 - Look at equilibrium conditions, no external field: a “built-in” electric field appears!



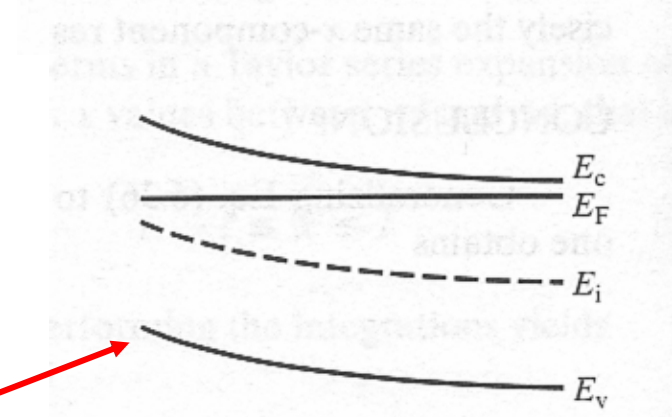
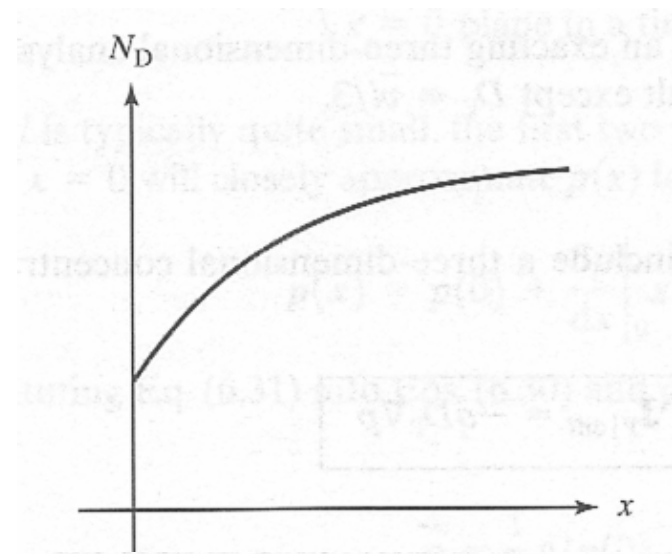
Non-uniform doping in equilibrium

- Under equilibrium conditions the Fermi level inside a material (or group of materials in intimate contact) is invariant as a function of position

$$\frac{dE_F}{dx} = \frac{dE_F}{dy} = \frac{dE_F}{dz} = 0$$

- A non-zero (“built-in”) electric field is established in nonuniformly doped semiconductors under equilibrium conditions

$$\begin{aligned} \mathcal{E} &= (1/q)(dE_C/dx) = \\ &= (1/q)(dE_i/dx) = \\ &= (1/q)(dE_V/dx) \end{aligned}$$

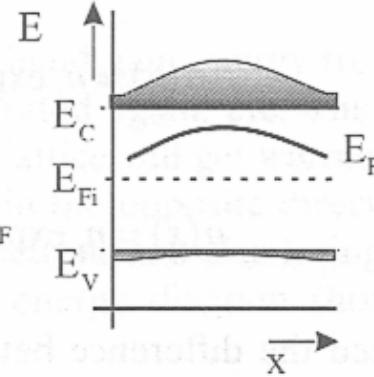
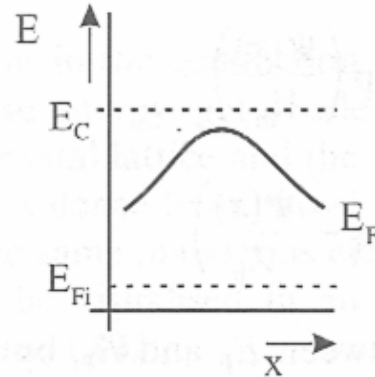
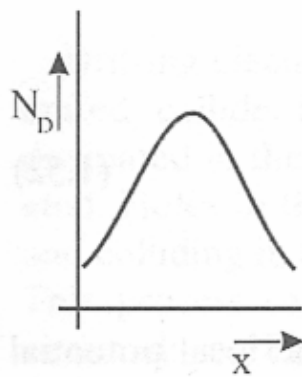


“band bending”, as for an external field; here the field is “built-in” (b)

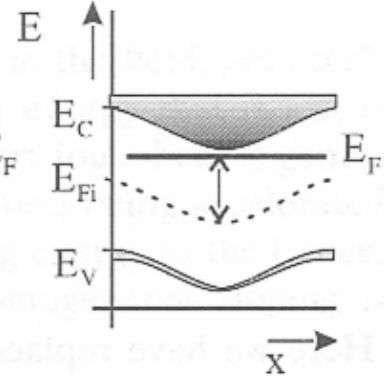


Non-uniform doping: an example

Donor concentration:



“band bending”:

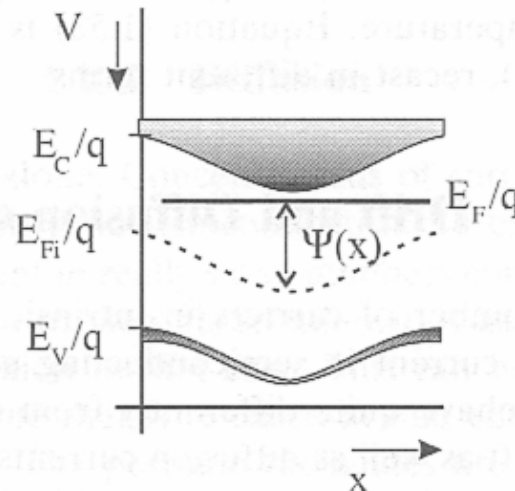


⇒ Built-in electric field:

$$\begin{aligned} \mathcal{E} &= (1/q)(dE_i/dx) = \\ &= (1/q)(d(E_F - E_i)/dx) = \\ &= -d\Psi/dx \end{aligned}$$

Electric potential

$$V(x) = \Psi(x) = (1/q)(E_F - E_i(x))$$



Equilibrium:

$$E_F = \text{constant}$$



Einstein relation - justification

- Non-uniform doping at equilibrium:
 - Built-in field $\mathcal{E} \Rightarrow$ drift; the drift current compensates diffusion (*net current density is zero at equilibrium*)! For electrons:

$$J_{n,drift} + J_{n,diff} = |q|\mu_n n \mathcal{E} + |q|D_n \frac{dn}{dx} = 0$$

$$n = N_C e^{(E_F - E_C)/kT}$$

$$\frac{dn}{dx} = \frac{dn}{dE_C} \frac{dE_C}{dx} = -\frac{1}{kT} n |q| \mathcal{E}$$

$$\mathcal{E} = \frac{1}{|q|} \frac{dE_C}{dx} \Rightarrow \frac{dE_C}{dx} = |q| \mathcal{E}$$

$$D_n = \left(\frac{kT}{|q|} \right) \mu_n$$

Valid also for non-equilibrium conditions !

$$|q|\mu_n n \mathcal{E} + |q|D_n \frac{dn}{dx} = |q| \mathcal{E} \left(\mu_n n - \frac{|q|}{kT} n D_n \right) = 0$$

Connection between $n(x)$ and built-in field



Einstein relation – numerical examples

- In the “non-degenerate” limit:

$$\frac{D_n}{\mu_n} = \frac{kT}{q} \qquad \frac{D_p}{\mu_p} = \frac{kT}{q}$$

- Typical sizes of mobility and diffusivity:

$$T = 300K \quad \Rightarrow \quad \frac{kT}{q} \approx 0.026 \text{ V}$$

$$\mu_n = 1000 \text{ cm}^2 / \text{Vs} \quad \Rightarrow \quad D_n \approx 26 \text{ cm}^2 / \text{s}$$



Current density equations

- When an *external* electric field \mathcal{E} is present *in addition* to the concentration gradient: *no equilibrium!*
 - Both drift and diffusion currents will flow
 - The total current density is *different from zero* in this case!
- For electrons and holes: $J = J_n + J_p$

$$J_n = J_{n,drift} + J_{n,diff} = \underbrace{|q|\mu_n n \mathcal{E}}_{\text{drift}} + \underbrace{|q|D_n \frac{dn}{dx}}_{\text{diffusion}}$$

$$J_p = J_{p,drift} + J_{p,diff} = |q|\mu_p p \mathcal{E} - |q|D_p \frac{dp}{dx}$$



Carrier injection

Carrier injection - introduction

- “carrier injection” = process of introducing “excess” carriers in a semiconductor, so that: $np > n_i^2$
 - Optical excitation:
 - shine a light on a semiconductor crystal;
 - if the energy of the photons is $h\nu > E_g$, then
 - Photons absorbed
 - “excess” electron-hole *pairs* are created: $\Delta n = \Delta p$
 - Other methods:
 - Forward-bias a pn junction
 - ...
 - In an extrinsic semiconductor, the *relative* effect of $\Delta n = \Delta p$ is *very different* for “majority” and “minority” carriers, since $n \neq p$
 - Let us work out an example (n-type Si, $n > p$ at equilibrium)



Carrier injection

Example: n-type Si at 300K

thermal equilibrium

$$n_0 p_0 = n_i^2$$

$$n_i = 1.45 \times 10^{10} \text{ cm}^{-3}$$

$$n_0 \approx N_D = 10^{15} \text{ cm}^{-3}$$

$$p_0 \approx n_i^2 / N_D = 2.1 \times 10^5 \text{ cm}^{-3}$$

majority carriers

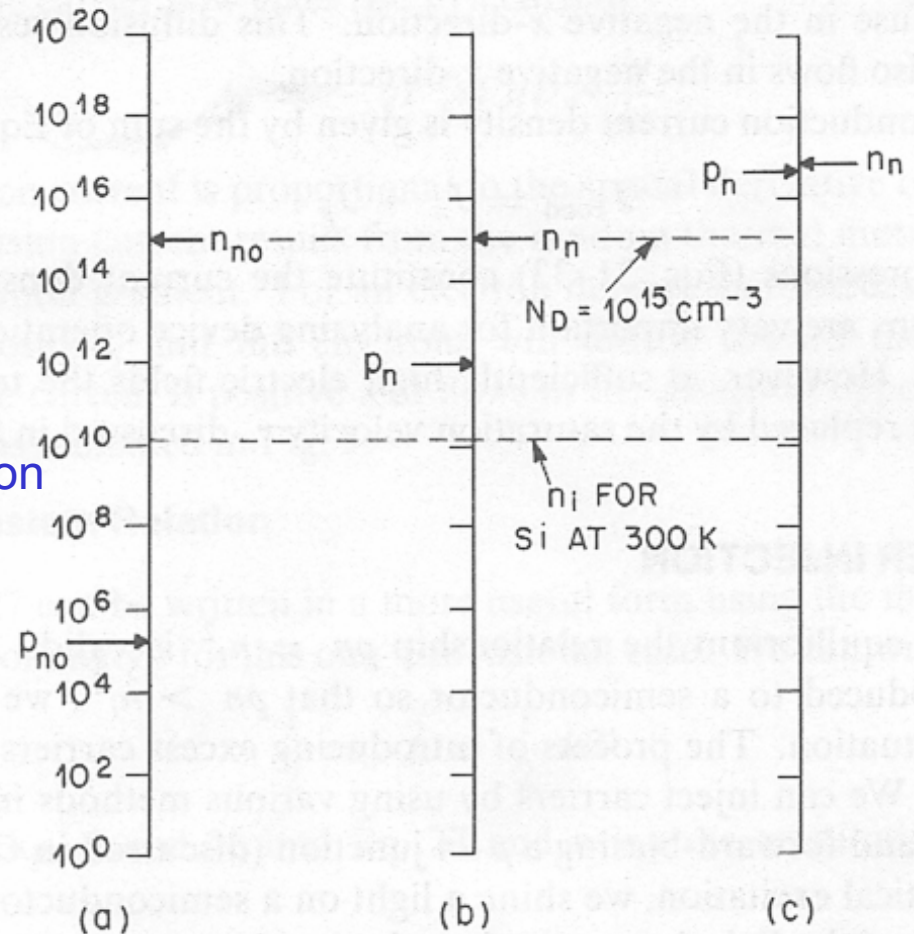
intrinsic concentration

minority carriers

thermal equilibrium

low injection

high injection



Carrier injection

Example: n-type Si at 300K

“excess” carriers
low-injection

$$\Delta n = \Delta p = 10^{12} \text{ cm}^{-3} \ll N_D$$

$$\Rightarrow np > n_i^2$$

$$n = n_0 + \Delta n \approx n_0$$

$$= 10^{15} + 10^{12} \approx 10^{15} \text{ cm}^{-3}$$

$$p = p_0 + \Delta p \approx \Delta p$$

$$= 10^5 + 10^{12} \approx 10^{12} \text{ cm}^{-3}$$

Large increase
in minority carriers

thermal
equilibrium

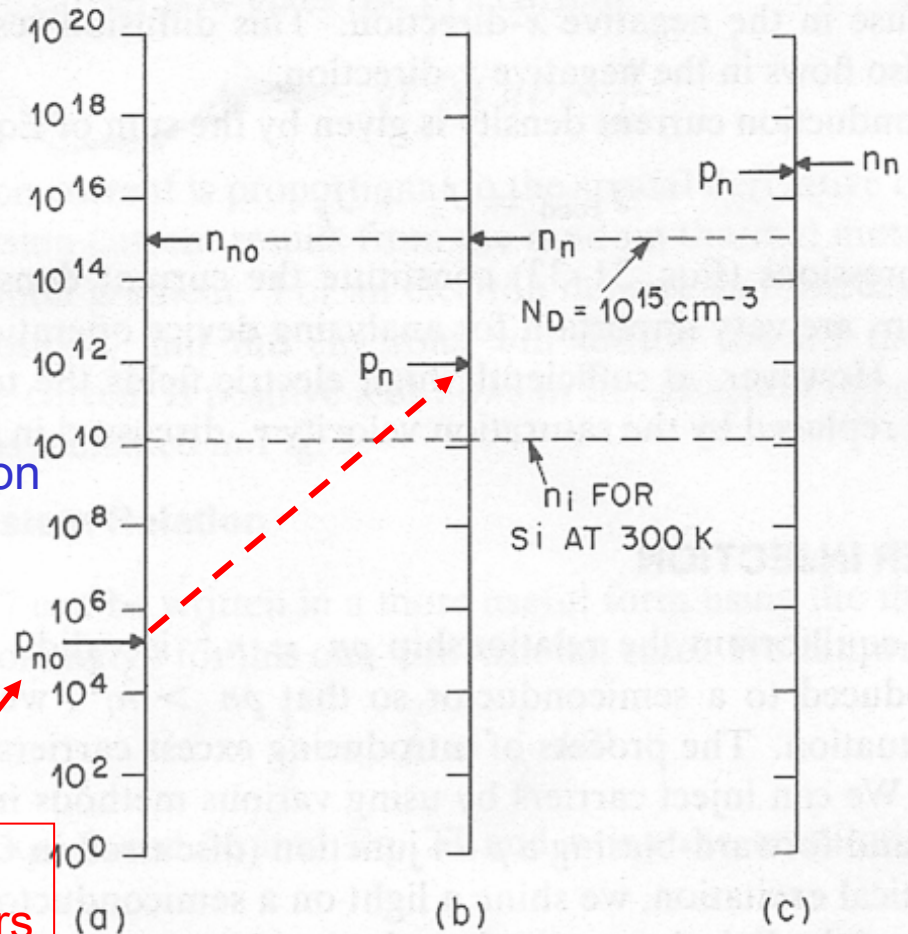
low
injection

high
injection

majority
carriers

intrinsic
concentration

minority
carriers



Carrier injection

Example: n-type Si at 300K

“excess” carriers
high-injection

$$\Delta n = \Delta p > N_D$$

$$\Rightarrow np > n_i^2$$

$$n = n_0 + \Delta n \approx \Delta n$$

$$p = p_0 + \Delta p \approx \Delta p$$

Large increase for both carriers
Similar concentrations

thermal
equilibrium

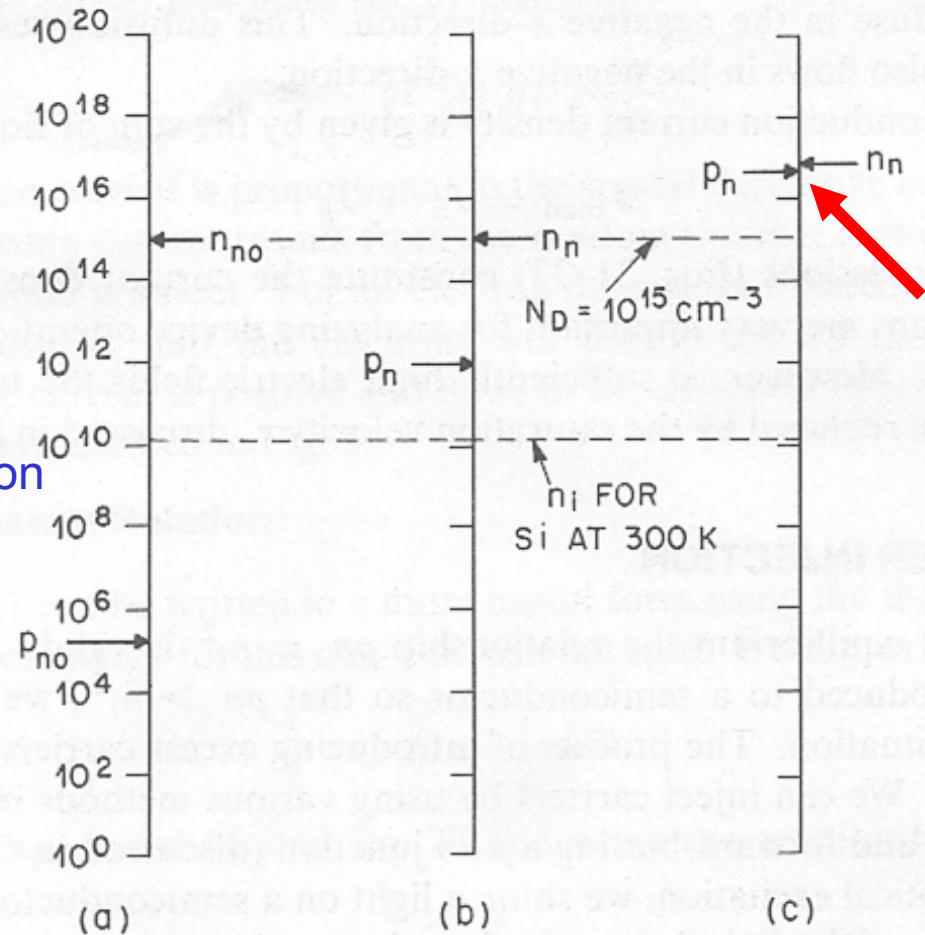
low
injection

high
injection

majority
carriers

intrinsic
concentration

minority
carriers



Carrier injection - summary

- “carrier injection” = process of introducing “excess” carriers in a semiconductor
- Several methods (optical, etc.)
- Low-level injection: relative effect on concentration
 - Negligible on majority carriers
 - Important for minority carriers (also called “minority carriers injection”)
- High-level injection
 - If very high, both concentrations become comparable
 - Sometimes encountered in device operation



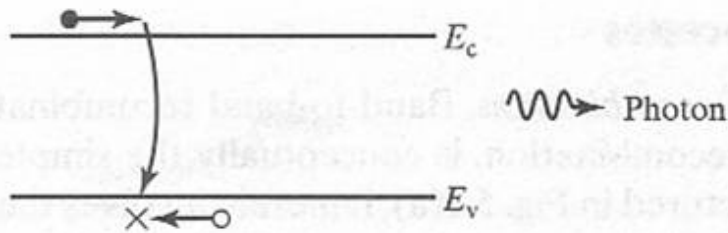
Generation and recombination processes

Generation and recombination: introduction

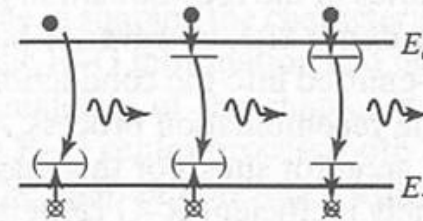
- Processes that tend to restore equilibrium ($np = n_i^2$) when it is disturbed ($np \neq n_i^2$); for instance:
 - After injection of excess carriers:
 - Recombination of injected minority carriers with majority carriers
- Recombination processes:
 - “Radiative” (with emission of a photon), “non-radiative”
 - “Direct” (dominant in direct-gap semiconductor), “indirect”
 - Surface effects, Auger recombination, ... many processes
- For each, the corresponding “inverse” generation exists
 - Thermal equilibrium: “detailed balance” separately for each one
 - Off-equilibrium: overall compensation (continuity equations)
- Qualitative introduction now; quantitative next lecture



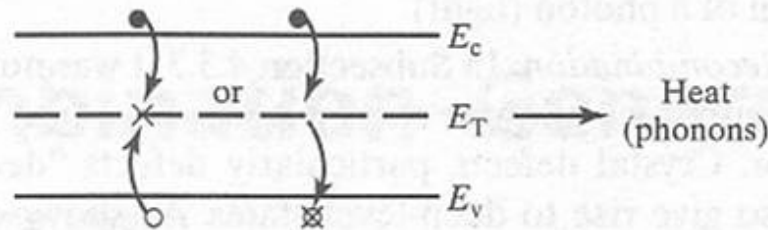
Recombination processes



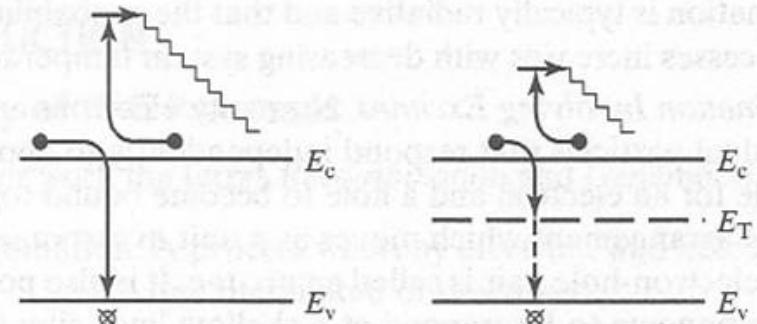
(a) Band-to-band recombination



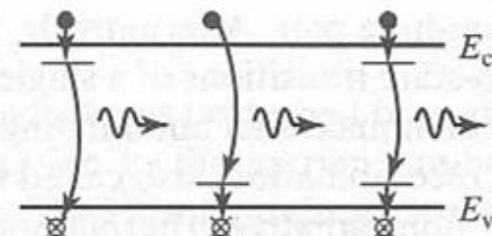
(d) Recombination involving excitons



(b) R-G center recombination



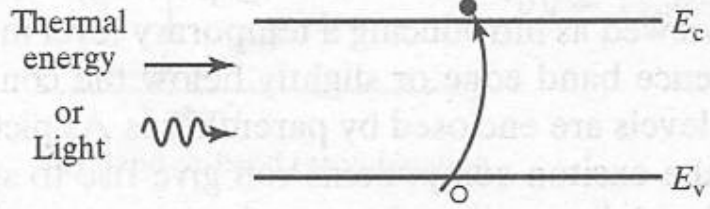
(e) Auger recombination
(Intrinsic) (Extrinsic)



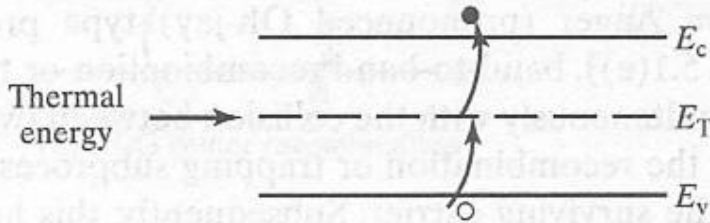
(c) Recombination via shallow levels



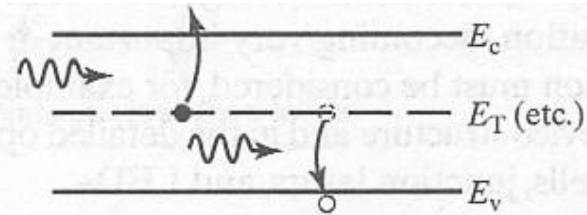
Generation processes



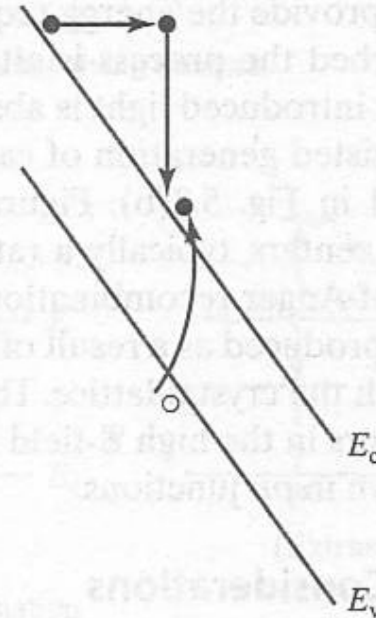
(a) Band-to-band generation



(b) R-G center generation



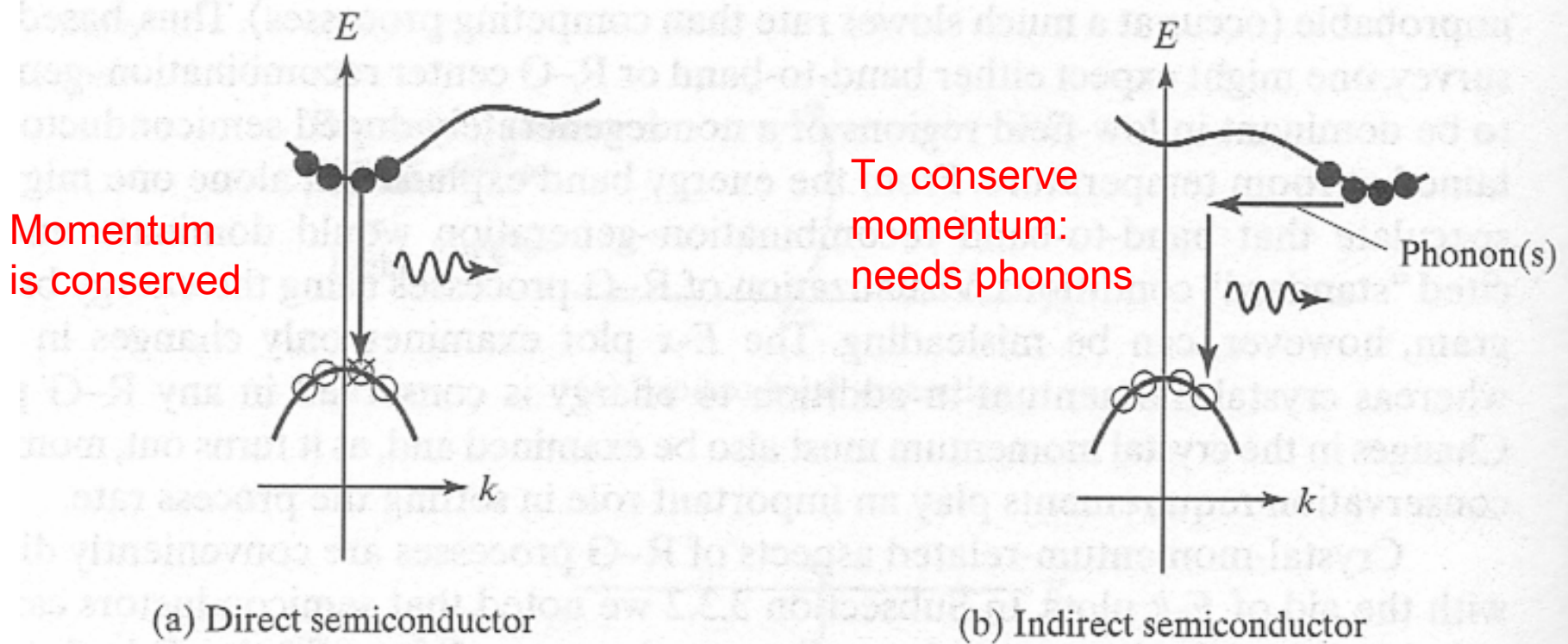
(c) Photoemission from band gap centers



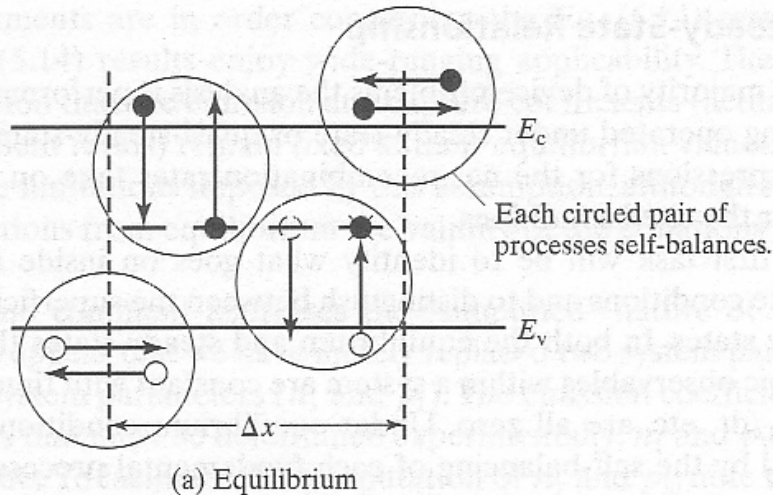
(d) Carrier generation via impact ionization

Energy and momentum!

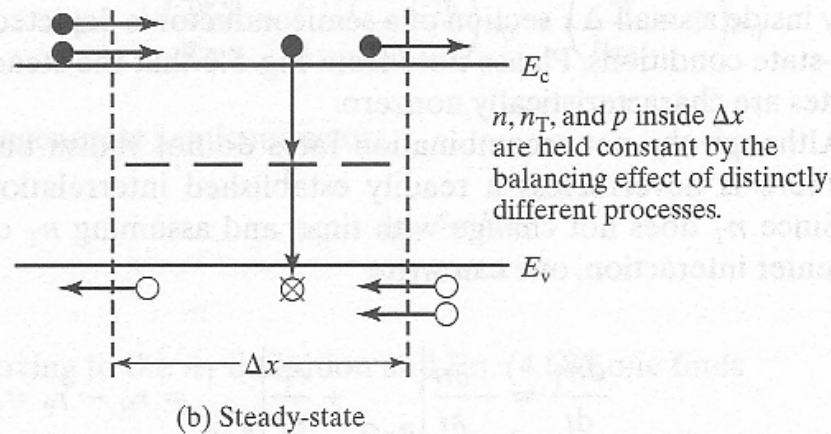
- Optical transitions in “direct” and “indirect” semiconductors



“Equilibrium” vs “steady state”



“Equilibrium”:
detailed balance,
for *each* process



“steady state”:
overall balance

Recombination and generation: summary

- Quick and qualitative survey of generation and recombination processes...
- Quantitative description of their rates and equations combining them together with drift and diffusion?
 - Next lecture!



Lecture 5 - summary



Lecture 5 – Items to be understood...

- Some items that require a deeper explanation:
 - photon
 - photon energy
 - Phonons
 - Excitons ?
 - Quantitative description of generation and recombination processes (theoretical, experimental)
 - Diffusivity, mobility: how can they be measured? How do they vary with doping, temperature, etc.?
 - What about degenerate semiconductors? What equations need to be modified?



Lecture 5 - Glossary

degenerate semiconductor	
non-degenerate semiconductor	
diffusion	
current density	
diffusivity	
mobility	
thermal voltage	
band bending	
carrier injection	
thermal equilibrium	
steady state	
detailed balance	
low injection	
high injection	
generation	
recombination	
radiative recombination	
non-radiative recombination	
direct R-G	
indirect R-G	
R-G centers	
Auger recombination	
surface recombination	



Lecture 5 - exercises

- **Exercise 5.1:** An intrinsic Si sample is doped with donors from one side such that $N_D = N_0 \exp(-ax)$. (a) Find an expression for the built-in electric field $E(x)$ at equilibrium over the range for which $N_D \gg n_i$. (b) Evaluate $E(x)$ when $a = 1 \mu\text{m}^{-1}$.
- **Exercise 5.2:** An n-type Si slice of thickness L is inhomogeneously doped with phosphorous donor whose concentration profile is given by $N_D(x) = N_0 + (N_L - N_0)(x/L)$. What is the formula for the electric potential difference between the front and the back surfaces when the sample is at thermal and electric equilibria regardless of how the mobility and diffusivity vary with position? What is the formula for the equilibrium electric field at a plane x from the front surface for a constant diffusivity and mobility?



Backup slides